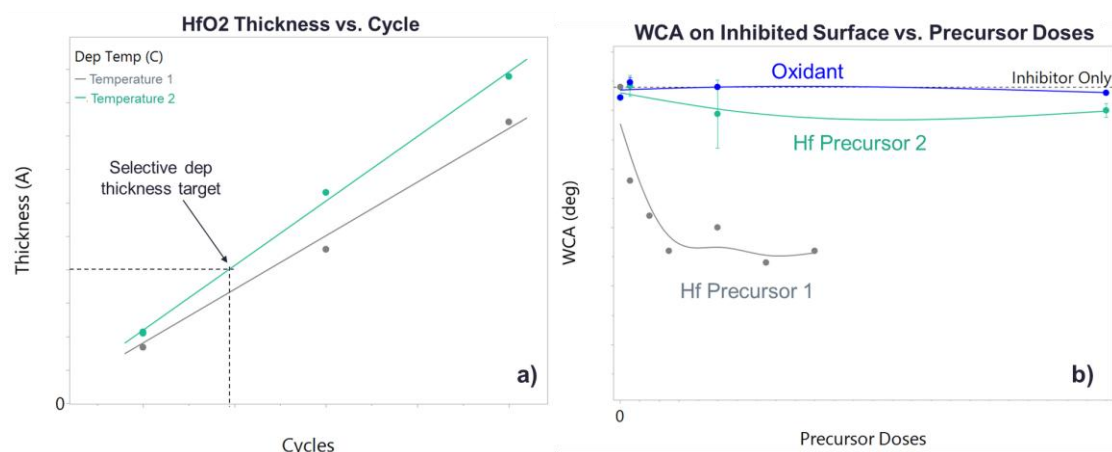


## Selective Deposition of HfO<sub>2</sub> Films – Supplemental Figure

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**Figure 1:** a) HfO<sub>2</sub> thermal ALD deposits linearly as a function of cycle on metal oxide blanket substrates. b) Different Hf precursors break down the inhibitor layer more quickly than others.